

## PALM INTRANET

Day : Monday  
Date: 3/8/2004  
Time: 14:53:01

## Inventor Information for 10/627894

Inventor Name	City	State/Country
WALDFRIED, CARLO	FALLS CHURCH	VIRGINIA
HAN, QINGYUAN	COLUMBIA	MARYLAND
ESCORCIA, ORLANDO	FALLS CHURCH	VIRGINIA
ALBANO, RALPH	COLUMBIA	MARYLAND
BERRY, IVAN L.	ELLICOTT CITY	MARYLAND
SHIOTA, ATSUSHI	USHIKU	JAPAN

Appln Info

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## PALM INTRANET

Day : Monday  
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## Inventor Name Search Result

Your Search was:

Last Name = SHIOTA

First Name = ATSUSHI

Application#	Patent#	Status	Date Filed	Title	Inventor Name 21
10726666	Not Issued	020	12/04/2003 <i>all</i>	INSULATION FILM <i>Product &amp; Comp</i> <i>no pre pub</i>	SHIOTA, ATSUSHI <i>IFW</i>
10627894	Not Issued	030	07/24/2003	FLUORINE-FREE PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	SHIOTA, ATSUSHI
10346560	Not Issued	030	01/17/2003	FLUORINE-FREE PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	SHIOTA, ATSUSHI
10307384	Not Issued	168	12/02/2002	PROCESS FOR PRODUCING SILICA-BASED FILM, SILICA-BASED FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI
10270066	Not Issued	168	10/15/2002	PROCESS FOR PRODUCING SILICA-BASED FILM, SILICA-BASED FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI
10255941	Not Issued	071	09/27/2002	STACKED FILM, INSULATING FILM AND SUBSTRATE FOR SEMICONDUCTOR	SHIOTA, ATSUSHI <i>IFW</i>
10252607	Not Issued	041	09/24/2002	METHOD OF FILM FORMATION, INSULATING FILM, AND SUBSTRATE FOR SEMICONDUCTOR	SHIOTA, ATSUSHI <i>IFW</i>
10252606	Not Issued	090	09/24/2002	STACKED FILM, METHOD FOR THE FORMATION OF STACKED FILM, INSULATING FILM, AND SUBSTRATE FOR SEMICONDUCTOR	SHIOTA, ATSUSHI <i>IFW</i>
10165324	Not Issued	071	06/10/2002	METHOD FOR THE FORMATION OF SILICA FILM, SILICA FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI <i>IFW</i>
10103996	Not Issued	041	03/25/2002	COMPOSITION FOR FILM FORMATION, METHOD OF FILM FORMATION, AND SILICA-BASED FILM	SHIOTA, ATSUSHI <i>IFW</i>
10094647	Not Issued	041	03/12/2002	METHOD OF FORMING DUAL DAMASCENE STRUCTURE	SHIOTA, ATSUSHI <i>IFW</i>
10014593	6558747	150	12/14/2001	METHOD OF FORMING INSULATING FILM AND PROCESS FOR PRODUCING SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI
09778822	6406794	150	02/08/2001	FILM-FORMING COMPOSITION	SHIOTA, ATSUSHI
09770289	Not Issued	041	01/29/2001	PROCESS FOR PRODUCING SILICA-BASED FILM, SILICA-BASED FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI <i>IFW</i>
09670547	6410151	150	09/27/2000	COMPOSITION FOR FILM FORMATION, METHOD OF FILM FORMATION, AND INSULATING FILM	SHIOTA, ATSUSHI
09669859	6410150	150	09/27/2000	COMPOSITION FOR FILM FORMATION, METHOD OF FILM FORMATION, AND INSULATING FILM	SHIOTA, ATSUSHI
09163008	6190833	150	09/30/1998	RADIATION-SENSITIVE RESIN COMPOSITION	SHIOTA, ATSUSHI

09126953	Not Issued	161	07/31/1998	LAMINATED MATERIAL FOR MULTI-LAYERED PRINTED CIRCUIT BOARDS AND MULTI-LAYERED PRINTED CIRCUIT BOARD USING THE SAME	SHIOTA , ATSUSHI
08713875	5773178	150	09/13/1996	PROCESS FOR PRODUCING A PATTERNED ANISOTROPIC POLYMERIC FILM	SHIOTA , ATSUSHI
08510867	5811504	150	08/03/1995	LIQUID CRYSTALLINE EPOXY MONOMER AND LIQUID CRYSTALLINE EPOXY RESIN CONTAINING MESOGEN TWINS	SHIOTA , ATSUSHI
08023471	Not Issued	166	02/25/1993	RESIN COMPOUND	SHIOTA , ATSUSHI

Inventor Search Completed: No Records to Display.

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Search Another: Inventor	<input type="text" value="shiota"/>	<input type="text" value="atsushi"/>	<input type="button" value="Search"/>

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*from overlapping case*

**PALM INTRANET**

Day : Monday  
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**Inventor Name Search Result**

Your Search was:

Last Name = ALBANO

First Name = RALPH

Application#	Patent#	Status	Date Filed	Title	Inventor Name 5
<i>W/ HQ</i> 10627894	Not Issued	030	07/24/2003	FLUORINE-FREE PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	ALBANO, RALPH
<i>N/ HQ</i> 10346560	Not Issued	030	01/17/2003	FLUORINE-FREE PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	ALBANO, RALPH
<i>removed this case</i> 09952649	Not Issued	061	09/14/2001	PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	ALBANO, RALPH
<i>removed these are previously removed</i> 09952398	Not Issued	071	09/14/2001	ULTRAVIOLET CURING PROCESS FOR POROUS LOW-K MATERIALS	ALBANO, RALPH
<i>removed this one</i> 09906276	Not Issued	071	07/16/2001	PLASMA CURING OF MSQ-BASED POROUS LOW-K FILM MATERIALS	ALBANO, RALPH

Inventor Search Completed: No Records to Display.

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albano	ralph	

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